

Advances in Direct Write Lithography

09. March 2021 – Online

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10:00 – 10:10	Welcome & Introduction
10:10 – 10:55	<p>Daniel Braun (Heidelberg Instruments) "MLA systems – fast prototyping without photo masks"</p> <p>The Maskless Aligner series was first introduced in 2015. Since then, the maskless technology has become firmly established in research labs worldwide as well as in many small to mid-volume micro fabrication facilities. Application areas include MEMS, microfluidics, micro-optics, sensors, electronic components and many more. This webinar will give you an insight into our maskless lithography technology with emphasis on our maskless aligner series..</p>
11:00 – 11:45	<p>Nils Goedecke (Heidelberg Instruments Nano) "NanoFrazor – A Nanolithography Tool for 2D & 3D devices"</p> <p>NanoFrazor lithography systems were developed as a first true alternative or extension to standard mask-less nanolithography methods like electron beam lithography (EBL). In contrast to EBL they are based on thermal scanning probe lithography (t-SPL). Here a heatable ultra-sharp probe tip with an apex of a few nm is used for patterning and simultaneously inspecting complex nanostructures.</p>

We are looking forward to meeting you there

Daniel, Nils & Tomasz

